

ABSTRACT

STRIPPING AND CLEANING COMPOSITIONS FOR REMOVAL OF THICK FILM RESIST

Stripping and cleaning compositions suitable for the removal of film resists include about 2-55% by weight of at least one alkanolamine or at least one morpholine or mixtures thereof; about 20-94% by weight of at least one organic solvent; and about 0.5-60% by weight water based on the total weight of the composition.